

IN THE SPECIFICATION

Please replace the paragraph at page 1, lines 16-25, with the following rewritten paragraph:

The present invention relates to a film (more particularly, a material constituting a film) crystallization apparatus and method, and a phase shift mask[[, the]]. The apparatus and method ~~of which~~ generate a crystallized film, e.g., a polycrystal or monocrystal film (semiconductor film), by irradiating a film to be subjected to crystallization processing, e.g., a polycrystal or amorphous film (e.g., a semiconductor film), with light rays having their phase modulated by using a phase shift mask, i.e., a phase shifter.